

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

April 23, 2004

(Use several sheets if necessary)

ATTORNEY DOCKET NO.
3194.1022-002
(7184-PA13C)APPLICATION NO.
10/692,018FIRST NAMED INVENTOR
Daniel Alvarez, Jr.FILING DATE
October 23, 2003

EXAMINER

CONFIRMATION NO.
8519GROUP
1724

U.S. PATENT DOCUMENTS

EXAM- INER INITIAL	REF. NO.	DOCUMENT NUMBER Number-Kind Code (if known)	ISSUE DATE / PUBLICATION DATE MM-DD-YYYY	NAME OF PATENTEE OR APPLICANT OF CITED DOCUMENT
HL	AA	5,685,895	11-11-1997	Hagiwara <i>et al.</i>
	AB	5,910,292	6-8-1999	Alvarez, Jr. <i>et al.</i>
	AC	6,059,859	5-9-2000	Alvarez, Jr. <i>et al.</i>
	AD	6,103,206	8-15-2000	Taylor, Jr. <i>et al.</i>
	AE	4,855,276	8-8-1989	Osborne <i>et al.</i>
	AF	5,607,647	3-4-1997	Kinthead
	AG	4,663,300	5-5-1987	Lester <i>et al.</i>
	AH	4,735,927	4-5-1988	Gerdes <i>et al.</i>
	AI	4,798,813	1-17-1989	Kato <i>et al.</i>
	AJ	4,869,735	9-26-1989	Miyazawa <i>et al.</i>
	AK	5,171,422	12-15-1992	Kirker <i>et al.</i>
	AA2	5,328,672	7-12-1994	Montreuil <i>et al.</i>
	AB2	5,430,000	7-4-1995	Timken
	AC2	6,114,268	9-5-2000	Wu <i>et al.</i>
	AD2	6,569,394 B2	5-27-2003	Fischer <i>et al.</i>
	AE2	6,576,587 B2	6-10-2003	Labarge <i>et al.</i>
	AF2	6,645,898 B2	11-11-2003	Alvarez, Jr. <i>et al.</i>
HL	AG2	6,391,090 B1	5-21-2002	Alvarez, Jr. <i>et al.</i>
	AH2			
	AI2			
	AJ2			
	AK2			
	AA3			
	AB3			
	AC3			

EXAMINER

Frank Lawrence

DATE CONSIDERED

11-9-04

PTO-1349 REPRODUCED

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

April 23, 2004

(Use several sheets if necessary)

 ATTORNEY DOCKET NO.
3194.1022-002
(7184-PA13C)

 APPLICATION NO.
10/692,018

 FIRST NAMED INVENTOR
Daniel Alvarez, Jr.

 FILING DATE
October 23, 2003

EXAMINER

 CONFIRMATION NO.
8519

 GROUP
1724

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER Country Code-Number-Kind Code (if known)	DATE MM-DD-YYYY	NAME OF PATENTEE OR APPLICANT OF CITED DOCUMENT	TRANSLATION YES NO	
72	AL	WO 88/02659	04-21-1988	Steuler-Industriewerke GmbH	X	
	AM					
	AN					
	AO					
	AP					
	AQ					
	AL2					
	AM2					
	AN2					
	AO2					
	AP2					
	AQ2					
	AL3					
	AM3					
	AN3					
	AO3					
	AP3					
	AQ3					
	AL4					
	AM3					
	AN4					
	AO4					
	AP4					
	AQ4					

EXAMINER

Frank Lawrence

DATE CONSIDERED

11-9-04

PTO-1449 REPRODUCED INFORMATION DISCLOSURE CITATION IN AN APPLICATION April 23, 2004 (Use several sheets if necessary)	ATTORNEY DOCKET NO. 3194.1022-002 (7184-PA13C)		APPLICATION NO. 10/692,018	
	FIRST NAMED INVENTOR Daniel Alvarez, Jr.		FILING DATE October 23, 2003	
	EXAMINER	CONFIRMATION NO. 8519	GROUP 1724	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
AR	HL	Dallas, Andrew J., <i>et al.</i> , "Protecting the DUV Process and Optimizing Optical Transmission", <i>Meterology, Inspection, and Process Control for Microlithography XIV</i> , Neal T. Sullivan, Editor, Proceedings of SPIE, Vol. 3998, pages 863-74 (2000).
AS	HL	Holmes, S. J., <i>et al.</i> , "Manufacturing with DUV Lithography", <i>IBM Journal of Research and Development</i> , Vol. 41, Optical Lithography (1997).
AT	HL	Kishkovich, Oleg, <i>et al.</i> , "Real-Time Methodologies for Monitoring Airborne Molecular Contamination in Modern DUV Photolithography Facilities", <i>SPIE Conference on Meterology, Inspection, and Process Control in Microlithography XIII</i> , Vol. 3677, pages 348-76 (March 1999).
AU	HL	Koshkovich, Oleg, <i>et al.</i> , "An Accelerated Testing Technique for Evaluating Performance of Chemical Air Filters for DUV Photolithographic Equipment", <i>SPIE Conference on Meterology, Inspection, and Process Control in Microlithography XIII</i> , Vol. 3677, pages 857-65 (March 1999).
AV	HL	MacDonald, Scott A., <i>et al.</i> , "Airborne Contamination of a Chemically Amplified Resist 1 Identification of Problem", <i>Chem. Mater.</i> , Vol. 5, pages 348-56 (1993).
AW	HL	Zhu, Sheng-Bai, "Contamination Control During Sh8pp8ng, Handling and Storage of Reticles", <i>Meterology, Inspection, and Process Control for Microlithography XIV</i> , Neal T. Sullivan, Editor, Proceedings of SPIE, Vol. 3998, pages 565-72 (2000).
AX	HL	<i>Ullmans' Encyclopedia of Industrial Chemistry, Completely Revised Fifth Edition</i> , Editors Barbara Elvers and Stephen Hawkins, Vol. 28A, pages 475-90 (1985).
AY	HL	<i>Kirk-Othmer Encyclopedia of Chemical Technology, Third Edition</i> , Vol. 15, pages 639-55, 1339-69 (1978).
AZ		
AR2		
AS2		
AT2		

EXAMINER Frank Lawrence	DATE CONSIDERED 11-9-04
----------------------------	----------------------------